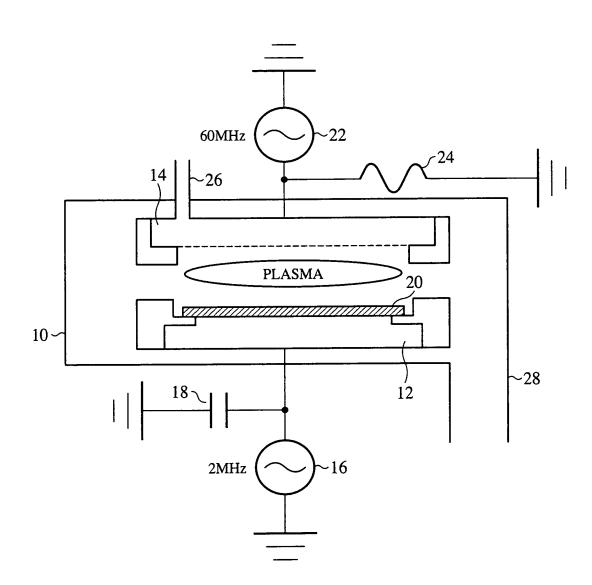
FIG. 1



Intle: METHOD FOR ETCHING ORGANIC INSULATING FILM AND METHOD ...
By: Kenichi HIGUCHI
Docket No.: 031110

FIG. 2

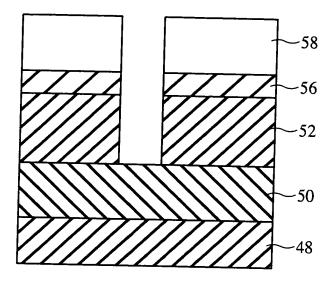
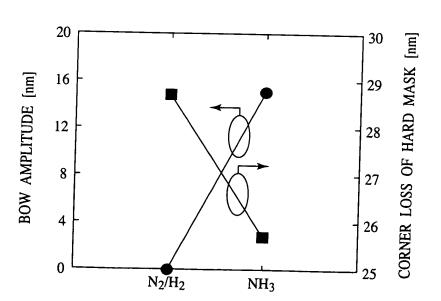
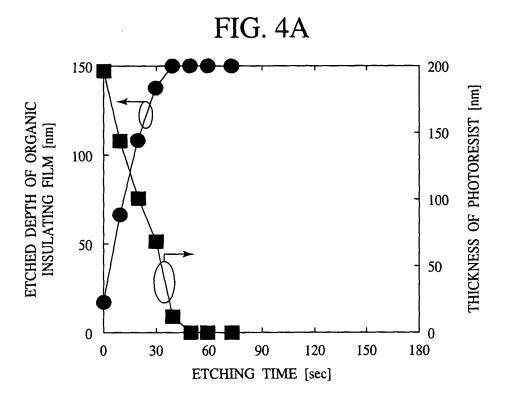
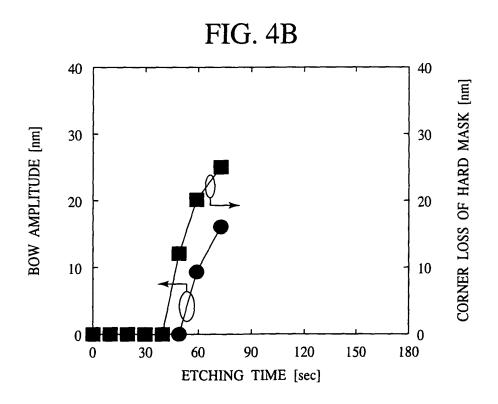


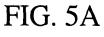
FIG. 3



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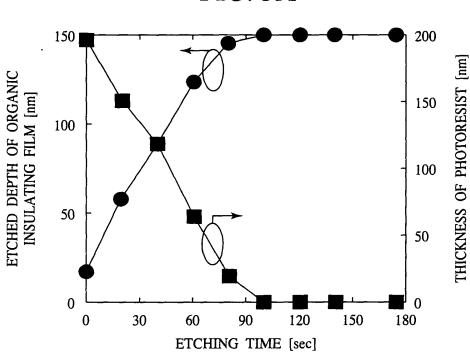
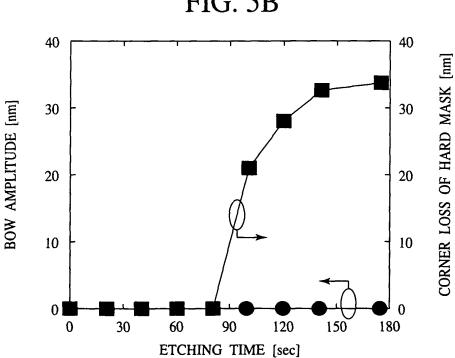
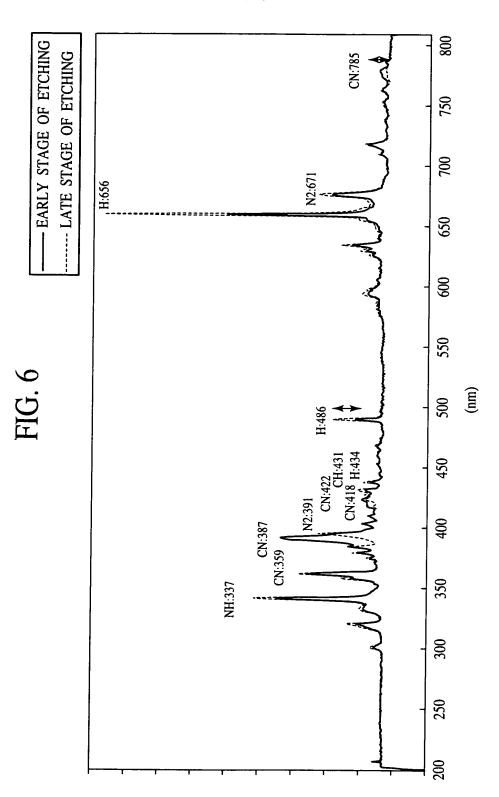


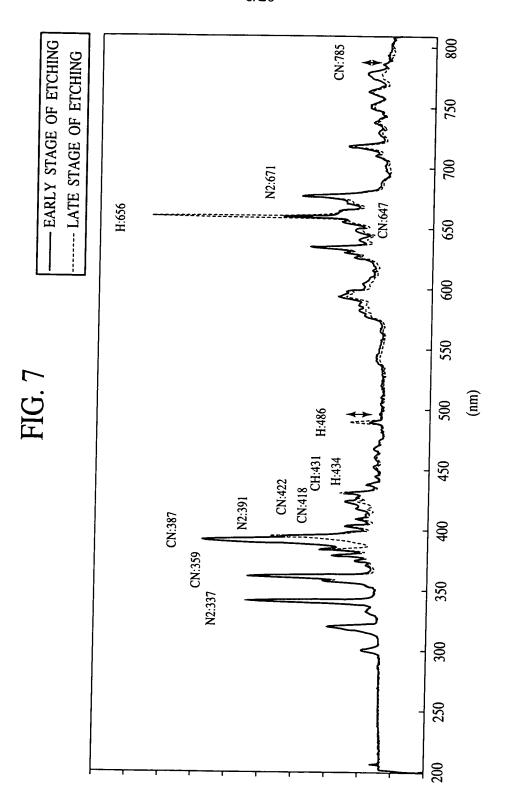
FIG. 5B



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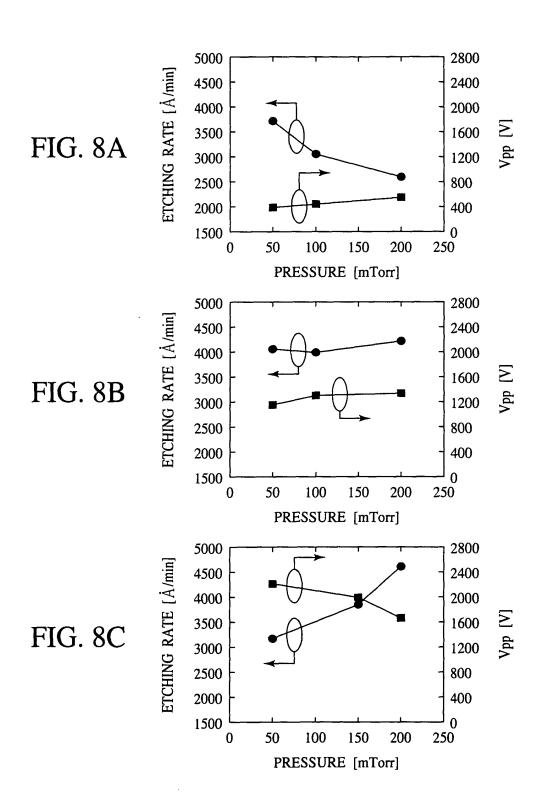
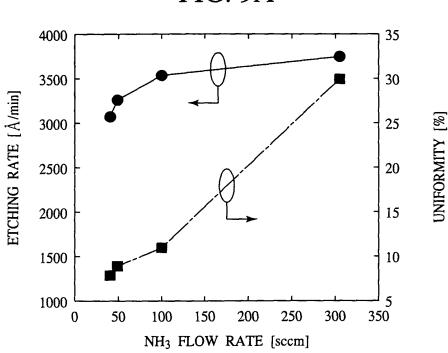


FIG. 9A





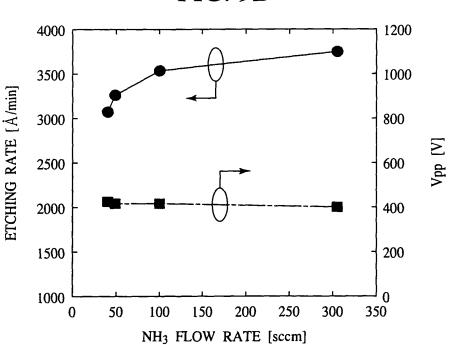
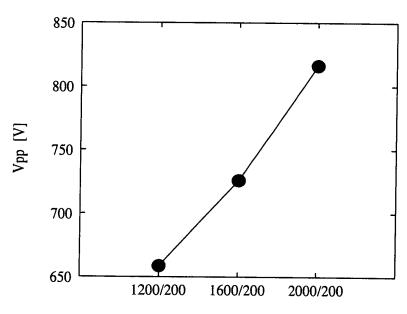
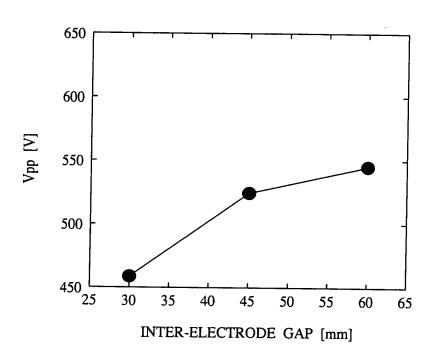


FIG. 10

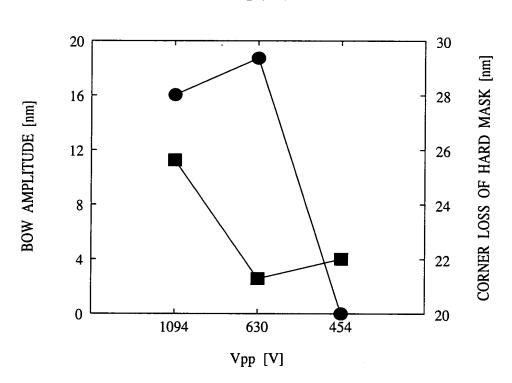


RF-POWER [W] (UPPER ELECTRODE/LOWER ELECTRODE)

FIG. 11







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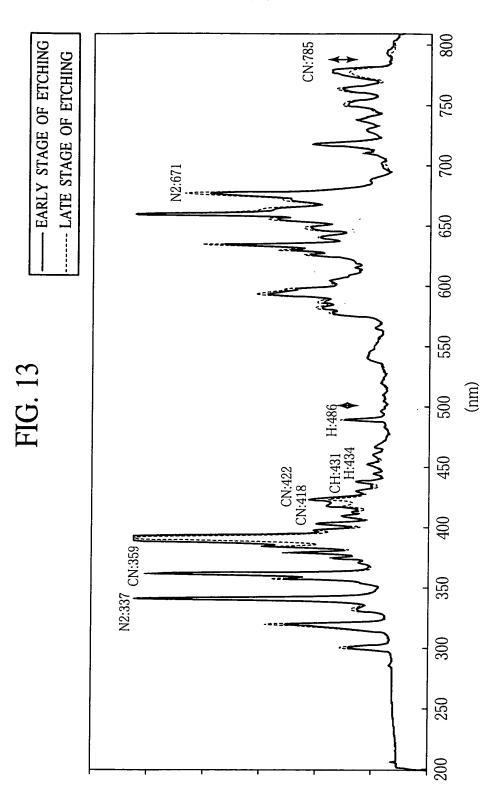


FIG. 14A

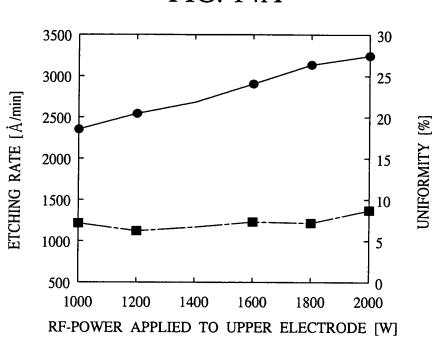
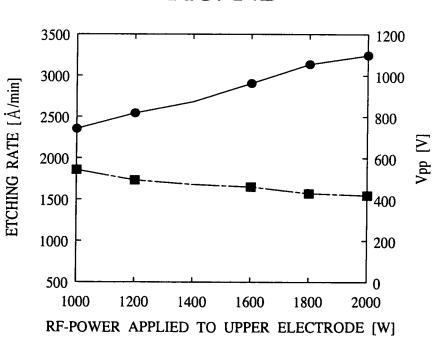


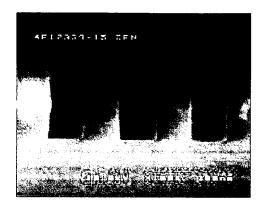
FIG. 14B



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FIG. 15A

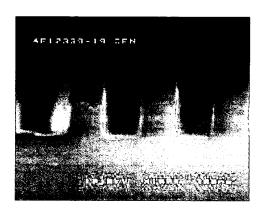


SiO

SiLK

SiO

FIG. 15B

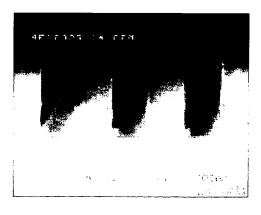


SiO

SiLK

SiO

FIG. 15C

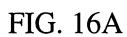


SiO

SiLK

SiO

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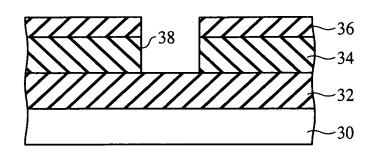
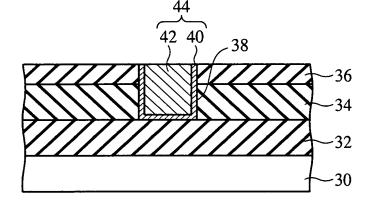
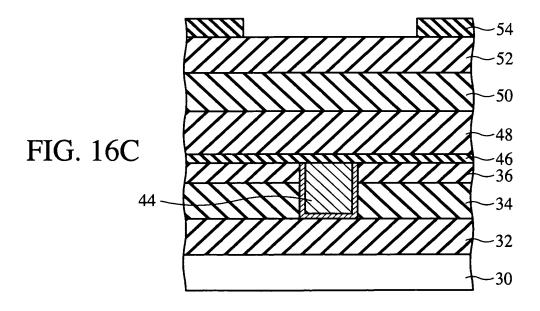
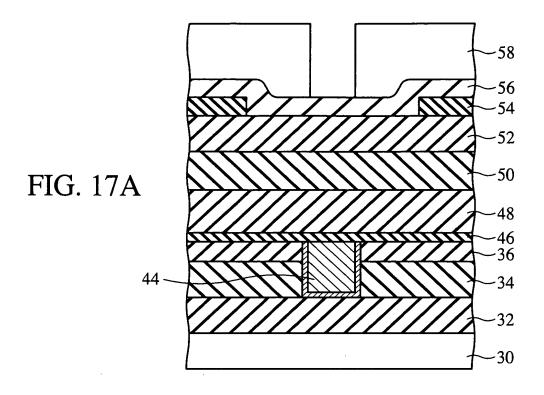
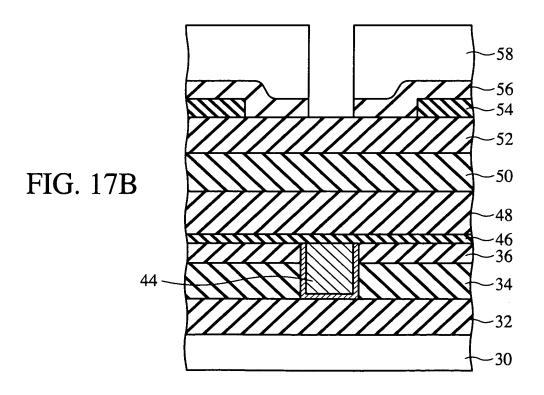


FIG. 16B

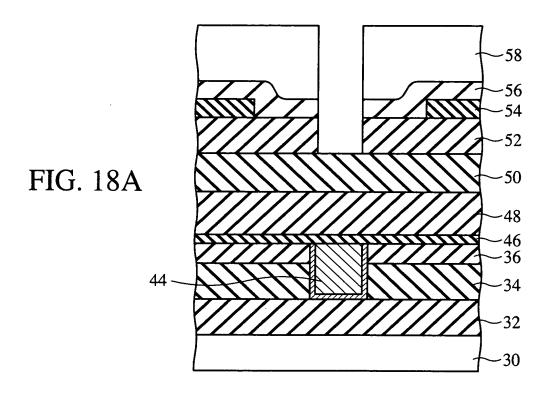








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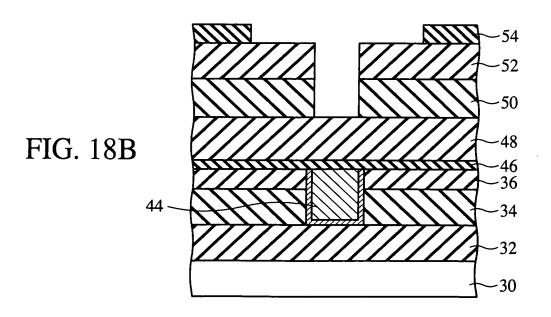


FIG. 19A

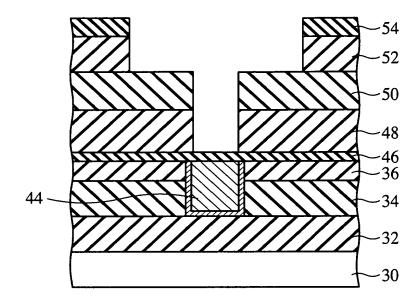


FIG. 19B

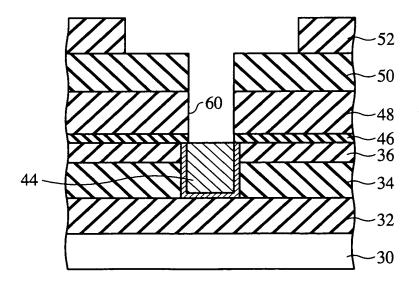


FIG. 20A

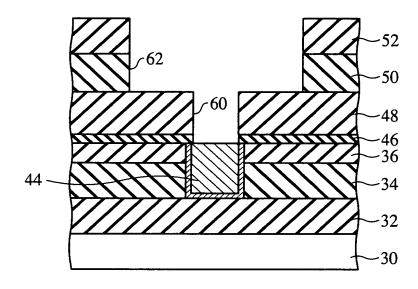
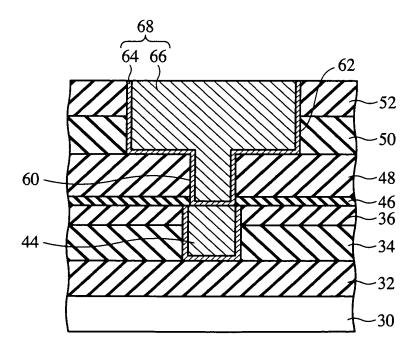


FIG. 20B



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FIG. 21A

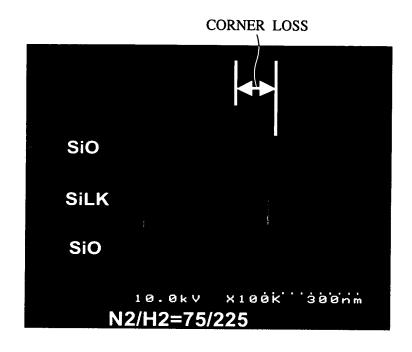


FIG. 21B

